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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of: Gennari

Attorney Docket No.:  
UCALP011X1/B02-005-3

Application No.: 10/716,266

Examiner: MERLINO, AMANDA H

Filed: November 17, 2003

Group: 2877


Title: METHOD OF LOCATING AREAS IN AN  
IMAGE SUCH AS A PHOTO MASK LAYOUT  
THAT ARE SENSITIVE TO RESIDUAL  
PROCESSING EFFECTS

Confirmation No.: 6483

**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as first-class mail on June 29, 2005 in an envelope addressed to the Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450.

Signed: \_\_\_\_\_

  
Laura M. Dean


**SEPARATE LETTER TO THE OFFICIAL DRAFTSMAN  
REQUESTING ENTERING OF FORMAL DRAWINGS  
(MPEP 608.02(p))**

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Enclosed are substitute (formal) drawings for the above-identified patent application. If the Draftsman has any question concerning these drawings, he or she is respectfully requested to contact the undersigned.

Respectfully submitted,  
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